

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	BRS	L1	3134	capacitor adj structure	USPAT	2002/08/14 14:58
2	BRS	L2	9845	(first adj conductive) same (second adj conductive)	USPAT	2002/08/14 15:01
3	BRS	L3	454	1 and 2	USPAT	2002/08/14 15:01
4	BRS	L4	3	(convert or converted or coverting or change or changing) same ((aluminum adj nitride) or (aluminum adj oxynitride)) same (dielectric adj material)	USPAT	2002/08/14 15:04
5	BRS	L5	85	(metallic adj aluminum) same (aluminum adj nitride)	USPAT	2002/08/14 15:22
6	BRS	L8	1	(transform or transforming) same ((metal or metallic) adj3 aluminum) same (AlN or AlON or AlO)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2002/08/14 15:25

US-PAT-NO: 6066427

DOCUMENT-IDENTIFIER: US 6066427 A

TITLE: Methods for making a charge generating layers  
comprising type I  
polymorph of titanyl phthalocyanine with reduced  
photosensitivity and  
photoconductors including the same

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The photoconductor substrate may be flexible, for example in the form of a flexible web or a belt, or inflexible, for example in the form of a drum. Typically, the photoconductor substrate is uniformly coated with a thin layer of metal, preferably aluminum which functions as an electrical ground plane. In a preferred embodiment, the aluminum is anodized to convert the aluminum surface into a thicker aluminum oxide surface. Alternatively, the ground plane member may comprise a metallic plate formed, for example, from aluminum or nickel, a metal drum or foil, or plastic film on which aluminum, tin oxide, indium oxide or the like is vacuum evaporated. Typically, the photoconductor substrate will have a thickness adequate to provide the required mechanical stability. For example, flexible web substrates generally have a thickness of from about 0.01 to about 0.1 microns, while drum substrates generally have a thickness of from about 0.75 mm to about 1 mm.

US-PAT-NO: 4636374

DOCUMENT-IDENTIFIER: US 4636374 A

TITLE: Method for manufacturing aluminum oxynitride refractory

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When the selected dross happens to have a low nitrogen content and the produced alumina is expected to have a relatively high nitrogen content, therefore, it is desirable that the aluminum dross to be used should be subjected in advance to a nitriding treatment to have its nitrogen content sufficiently heightened in advance. The nitriding of the dross can be effected, for example, by placing the dross in an alumina refractory container and heating it therein in an atmosphere of nitrogen gas at a temperature of about 600.degree. to 700.degree. C. By the applied heat, the metallic aluminum remaining in the dross begins to undergo a nitriding reacting and the heat of this reaction further elevates the temperature of the reaction system and, consequently, the metallic aluminum contained in the dross is substantially completely converted into AlN, with the result that the nitrogen content of the dross is increased.